

L Number	Hits	Search Text	DB	Time stamp
1	158	(filter\$5 near10 (circulat\$5 or recirculat\$6) near5 bath) and (semiconductor or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/09 10:53
2	69	(filter\$5 near10 (circulat\$5 or recirculat\$6) near5 bath) same (semiconductor or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/09 10:53
27	24	(roland near2 brunner or helmut near2 schwenk or johann near2 zach).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/09 17:11
-	195	((sequenc\$4 or sequent\$6) near4 process\$5) and 438/\$.ccls. and (ozone or "o.sub.3") and (hcl or hydrochlor\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:18
-	51	((sequenc\$4 or sequent\$6) near4 process\$5) and 438/\$.ccls. and (ozone or "o.sub.3") same (hcl or hydrochlor\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:19
-	23	((sequenc\$4 or sequent\$6) near4 process\$5) same ("without" near5 rins\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:19
-	217	filter\$5 near10 (return\$5 or (circulat\$5 or recirculat\$6)) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 15:45
-	41	filter\$5 near10 (return\$5 or (circulat\$5 or recirculat\$6)) same (bath) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 16:04
-	61	filter\$5 near15 bath and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 16:02
-	24	(roland near2 brunner or helmut near2 schwenk or johann near2 zach).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 16:03
-	3	((roland near2 brunner or helmut near2 schwenk or johann near2 zach).in.) and filter\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 16:03
-	41	filter\$5 near10 (circulat\$5 or recirculat\$6) same bath and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 16:05
-	2202	filter\$5 near10 (circulat\$5 or recirculat\$6) same bath	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 16:05
-	299	(filter\$5 near10 (circulat\$5 or recirculat\$6) same bath) and (semiconductor or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/07 16:05

-	101	(filter\$5 near10 (circulat\$5 or recirculat\$6) same bath) same (etch\$5 or rins\$5 or treat\$5) and (semiconductor or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/09 10:53
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